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(54) Title: A TARGET MATERIAL, A SOURCE, AN EUV LITHOGRAPHIC APPARATUS AND A DEVICE MANUFACTURING METHOD USING THE SAME

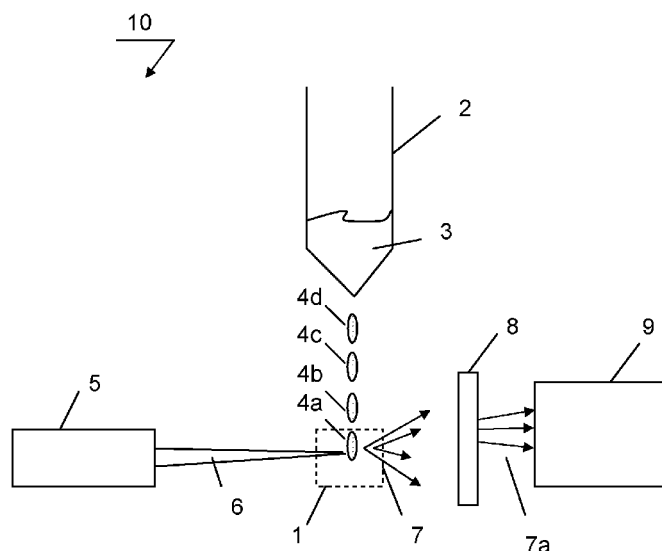


Fig. 2

(57) Abstract: A target material is configured to be used in a source constructed and arranged to generate a radiation beam having a wavelength in a 6.8 nm range. The target material includes a Gd-based composition configured to modify a melting temperature of Gd, or Tb, or a Tb-based composition configured to reduce a melting temperature of Tb.



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